

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2078	semiconductor and (plasma adj4 doping)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/18 10:15
L2	671	1 and ((dop\$3 or impurity) adj concentration)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/18 10:18
L3	638	2 and (below or under)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/18 10:37

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	0	(plasma and doping and substrate and dopant and concentration and peripher\$2 and planar and parallel). clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/18 15:48